	Hits	Search Text	DBs
47	0	((resist or photoresist) near16 pattern$4) and ((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE or ash$4)) and ((resist or photoresist) same strip$6 same (resid$4 or remain$5) same (amino$4ethanol near20 glycon near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
48	0	((resist or photoresist) same strip$6 same (resid$4 or remain$5) same (amino$4ethanol near20 glycon near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
49	0	((resist or photoresist) same strip$6 same (amino$4ethanol near20 glycon near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
50	11	((resist or photoresist) same strip$6 same (amino$4ethanol near20 glycol near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
51	3	((resist or photoresist) same strip$6) and (strip$4 same (amino$4 near4 ethanol near20 glycol near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
52	1	((resist or photoresist) near16 pattern$4) and ((Aluminum or TFT or transistor or Ti or titanium or Mb or molybdenum or Ta or tantulum or tungsten or metal$4 or conductive or gate) same (resist or photoresist) same (pattern$3 or mask) same (etch$4 or RIE or ash$4)) and ((resist or photoresist) same strip$6 same (resid$4 or remain$5) same (amino$4ethanol near20 glycol near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
53	11	((resist or photoresist) same strip$6) and (strip$4 same (amino$4ethanol near20 glycol near4 ether))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
54	25	((resist or photoresist) same strip$6) and (strip$4 same ((amino$4ethanol near20 glycol near4 ether) or (Nagase near4 strip$4)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB